



NOTES

1. COATING(S1): HIGH ENERGY LASER LINE COATING
Rs, Rp > 99% @ 532 nm, 45° AOI
2. CLEAR APERTURE(S1): > 90% CA
3. SURFACE QUALITY(S1): 20/10(S/D)
4. SURFACE FLATNESS(S1): $\lambda/6$ @ 633 nm
5. PARALLELISM(S1, S2): < 3 arcmin
6. CHAMFER: < 0.2 mm, 45°
7. THICKNESS TOLERANCE: ± 0.25 mm
8. DIAMETER TOLERANCE: $+0/-0.1$ mm
9. OTHER SURFACES: FINE GROUND
10. DAMAGE THRESHOLD: $8\text{J}/\text{cm}^2$, 532 nm, 10 ns, 20 Hz

DRAWING PROJECTION			LBTEK			
	NAME	DATE	LPM10-532-HP			
DRAWN	LZHOU	Aug. /5th/24	HIGH ENERGY LASER LINE MIRROR $\text{Ø} 25.4 \text{ mm} \times 6.0 \text{ mm}, 532 \text{ nm}$			
APPROVAL	WCHENG	Aug. /5th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	6.7 g	2:1	A